

Electronic Supplementary Information

Spontaneous nanoscale polymer solution patterning using solvent evaporation driven double-dewetting edge lithography

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S1. A movie file of the solvent driven double-dewetting lithography process

A 1 wt% PMMA solution in chlorobenzene is dropped onto a surface engineered substrate with 50 μm wide hydrophilic line regions at a 300 μm space. The solution covers the hydrophilic line regions spontaneously and solute aggregates at the edges of the line pattern with the solvent evaporation via coffee stain effect. The whole processes are accomplished in 1 sec.



S1. DDEL_move.avi (click on the black area to play the movie)